

Form PTO-1449

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

TSMC-02-992

Application Number

10/723,236

Applicant

Chun Hsien Lin et al.

Filing Date

11/26/03

Group Art Unit

U. S. PATENT DOCUMENTS

| EXAMINER INITIAL | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | PLNO DATE IF APPROPRIATE |
|---------------------|-----------------|----------|---------------|-------|----------|-----------------------------|
| W | 6555477 | 4/29/03 | Lu et al. | 438 | 692 | 5/22/02 |
| | 6372632 | 4/16/02 | Yu et al. | 438 | 634 | 1/24/00 |
| | 6405144 | 6/11/02 | Toprac et al. | 702 | 84 | 1/18/00 |
| | 6148239 | 11/14/00 | Funk et al. | 700 | 1 | 12/12/97 |
| | 6335286 | 1/1/02 | Lansford | 438 | 692 | 5/9/00 |
| | 5719495 | 2/17/98 | Maslehi | 324 | 158.1 | 6/5/96 |
| | 6528818 | 3/4/03 | Satya et al. | 257 | 48 | 8/25/00 |
| | 6514858 | 2/4/03 | Hause et al. | 438 | 640 | 4/9/01 |
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FOREIGN PATENT DOCUMENTS

| DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | Translation | |
|-----------------|------|---------|-------|----------|-------------|----|
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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|---|---|
| W | J. Zhang et al., "Automated Process Control of Within-Wafer and Wafer-to-Wafer Uniformity in Oxide CMP," [Online] March 2002, CMP MIC [retrieved on Jan 27, 2003] retrieved from URL: http://www.appliedmaterials.com/search97cgi/s97.cgi . |
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EXAMINER

Wilson

DATE CONSIDERED

9/15/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant